

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Prior Application: N. HASEGAWA et al
Serial No. 10/096,599
Filed: March 14, 2002

Group Art Unit: 1756
Examiner: S. Rosasco
For: PHOTOMASK AND PATTERN FORMING METHOD
EMPLOYING THE SAME

PRELIMINARY AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 13, 2004

Sir:

Prior to examination, please amend the above application
as follows.